IN THE CLAIMS

Please amend the following claims which are pending in the present application:

1. (Currently amended) A method, comprising:

adding a halogen substituted silicon hydride and a nitrogen-containing precursor to a first chamber;

adding the halogen substituted silicon hydride and the nitrogencontaining precursor to an organic solvent in a second chamber coupled to the first chamber;

applying a thermal energy to the halogen substituted silicon hydride and the nitrogen-containing precursor;

setting an operating temperature of the first chamber below 550 °C, and depositing a silicon nitride layer on a substrate disposed in the first chamber at the operating temperature.

- 2. (Cancelled)
- 3. (Currently amended) The method of claim 21, wherein the halogen substituted silicon hydride has the general formula:

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SiH_aX_{4-a}

where a is an integer less than or equal to three and greater than or equal

to one, and

X is a halogen.

4. (Withdrawn) The method of claim 2, wherein the halogen substituted silicon

hydride has the general formula;

SiX₄

where X is a halogen.

5. (Withdrawn) The method of claim 2, wherein the halogen substituted silicon

hydride has the general formula:

SiH_aX_bR_c

where a is an integer less than or equal to three and greater than or equal

to zero,

where b is an integer less than or equal to three and greater than or equal

to zero,

where *c* is an integer less than or equal to three and greater than or equal

to zero,

where the sum of a, b, and c is equal to four,

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where X is a halogen, and

where R is an alkyl group.

6. (Original) The method of claim 1, wherein adding further comprises reacting a

halogen substituted disilicon hydride with a nitrogen source.

7. (Withdrawn) The method of claim 6, wherein the halogen substituted disilicon

hydride has the general formula:

Si₂H_aX_{6-a}

where a is less than or equal to five and greater than or equal to one, and

where X is a halogen.

8. (Withdrawn) The method of claim 6, wherein the halogen substituted disilicon

hydride has the general formula:

Si₂X₆

where X is a halogen.

9. (Withdrawn) The method of claim 6, wherein the halogen substituted disilicon

hydride has the general formula:

Si₂H_aX_bR_c

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where a is an integer less than or equal to five and greater than or equal to

zero,

where b is an integer less than or equal to five and greater than or equal to

zero,

where *c* is an integer less than or equal to five and greater than or equal to

zero,

where the sum of a, b, and c is equal to six,

where X is a halogen, and

where R is an alkyl group.

10. (Cancelled)

11. (Withdrawn) The method of claim 10, wherein the silicon source is selected

from the group consisting of linear silazanes, branched silazanes, partially

substituted aminosilanes with diamene ligands, fully substituted aminosialnes

with diamene ligands, silyl cyclopropane, silyl cyclobutane, and halogenated

aminosilanes.

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13 - 27. (Cancelled)

28. (New) The method of claim 1, wherein the concentration of the silicon precursor is less than or equal to 0.5M and the concentration of the nitrogen precursor is less than or equal to 1.0M.

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